



### **ARCHIVE 2007**

2007

### **EXPLORING HANDLER, SOCKET & DEVICE INTERFACING**

### "The Importance of the Mechanical Interface in Final Test Efficiency"

Mark Stenholm Antares Advanced Test Technologies

### "Effects of Handler Insertion Variations on Contactor Performance for Pb-Free Devices"

Jeff Sherry Johnstech International Corporation

"Contacting Solution for Optical Sensor IC – HD DVD Application"

Gerhard Gschwendtberger

Multitest elektronische Systeme GmbH

### **COPYRIGHT NOTICE**

The papers in this publication comprise the proceedings of the 2007 BiTS Workshop. They reflect the authors' opinions and are reproduced as presented , without change. Their inclusion in this publication does not constitute an endorsement by the BiTS Workshop, the sponsors, BiTS Workshop LLC, or the authors.

There is NO copyright protection claimed by this publication or the authors. However, each presentation is the work of the authors and their respective companies: as such, it is strongly suggested that any use reflect proper acknowledgement to the appropriate source. Any questions regarding the use of any materials presented should be directed to the author/s or their companies.

All photographs in this archive are copyrighted by BiTS Workshop LLC. The BiTS logo and 'Burn-in & Test Socket Workshop' are trademarks of BiTS Workshop LLC.

BiTS Workshop 2007 Archive



Exploring Handler, Socket & Device Interfacing

# The Importance of the Mechanical Interface in Final Test Efficiency

### 2007 Burn-in and Test Socket Workshop



March 11 - 14, 2007



Mark Stenholm Antares Advanced Test Technology



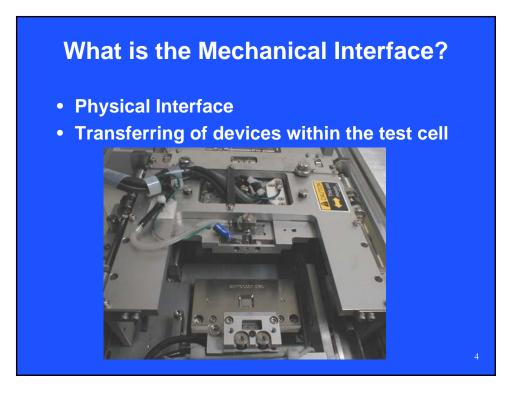


Exploring Handler, Socket & Device Interfacing

### **Test Interfaces**

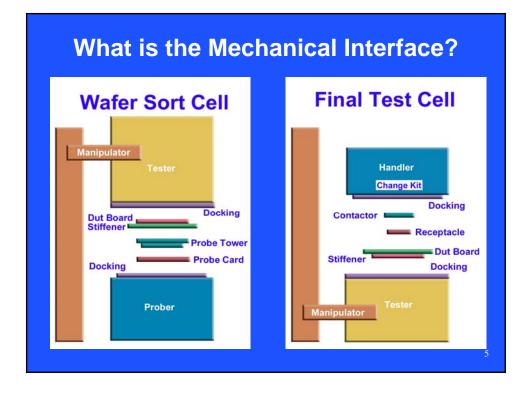
But the success or failure of the Mechanical Interface is equally important

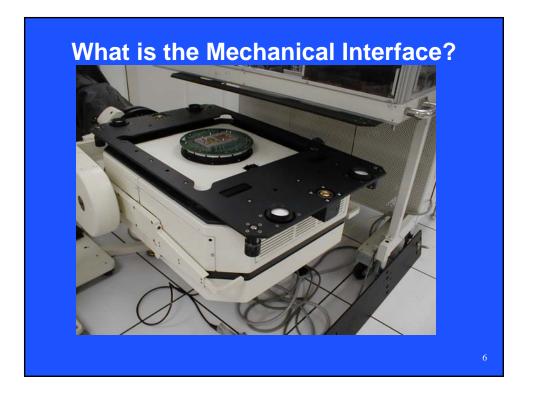






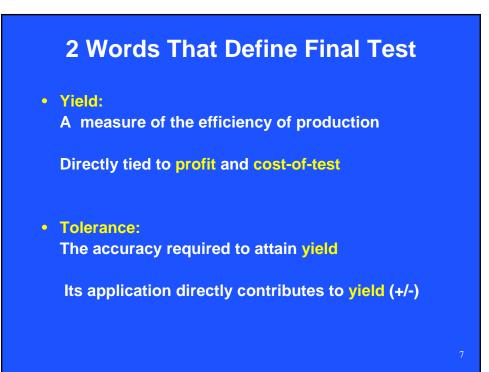
Exploring Handler, Socket & Device Interfacing

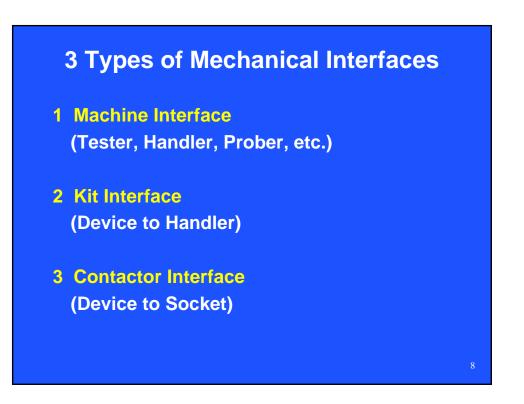






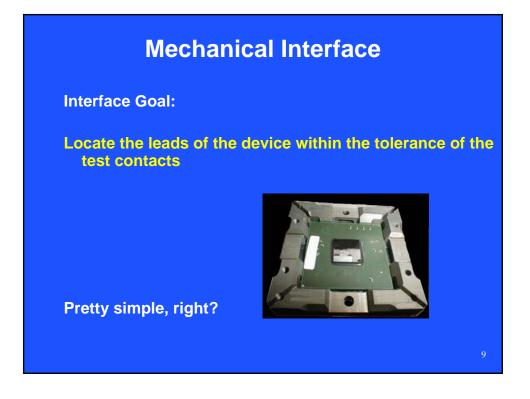
Exploring Handler, Socket & Device Interfacing







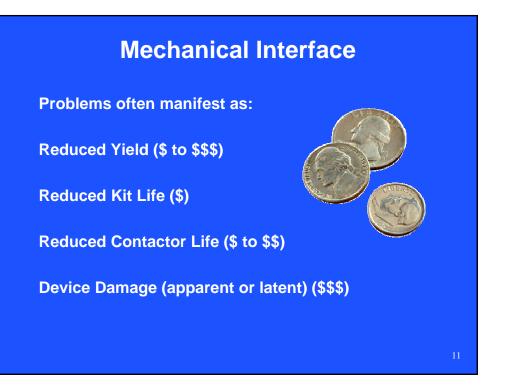
Exploring Handler, Socket & Device Interfacing

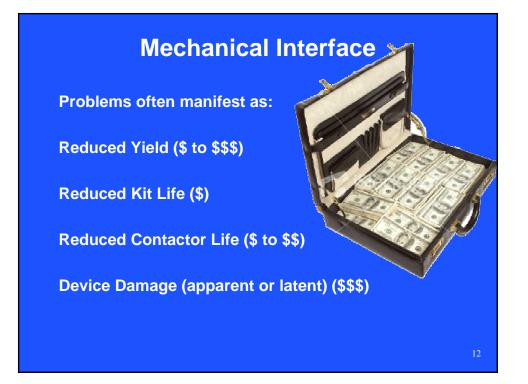


# <section-header><text><text><text><text><text><text>



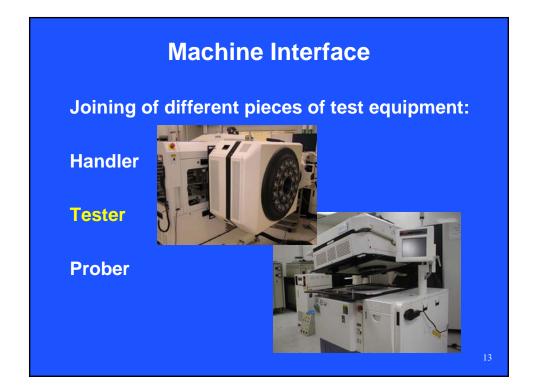
Exploring Handler, Socket & Device Interfacing

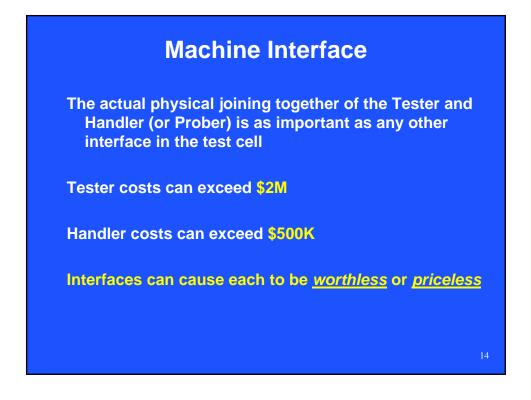






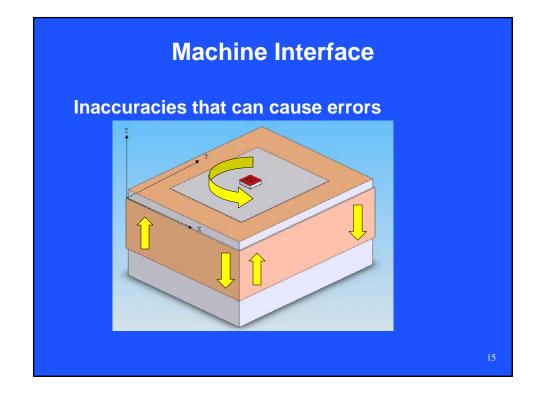
Exploring Handler, Socket & Device Interfacing

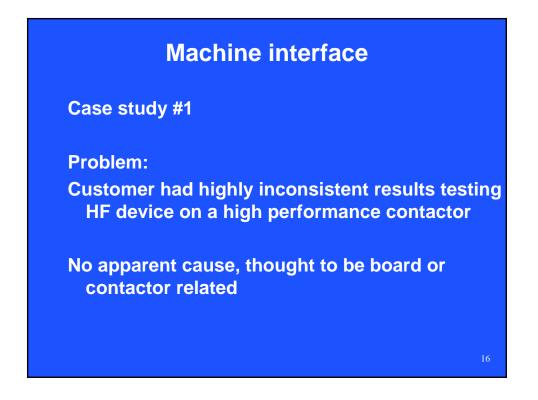






Exploring Handler, Socket & Device Interfacing

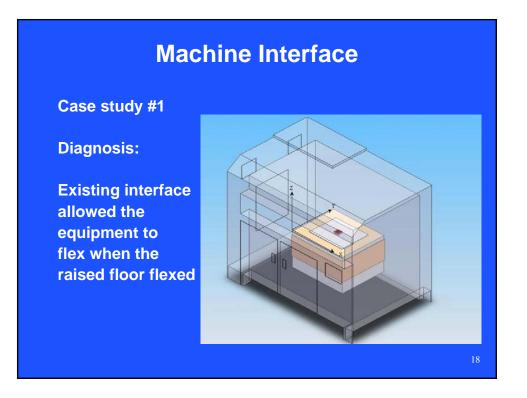






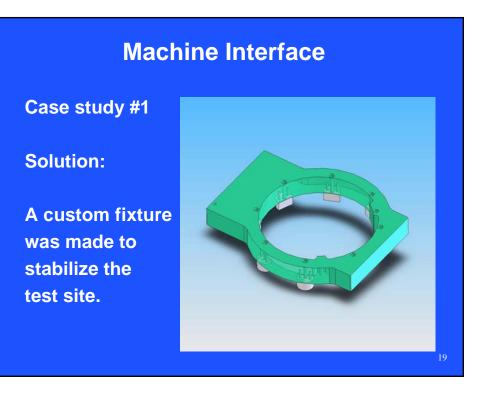
Exploring Handler, Socket & Device Interfacing

# <section-header><section-header><text><text><text><text>





Exploring Handler, Socket & Device Interfacing



### **Machine Interface**

Case study #1

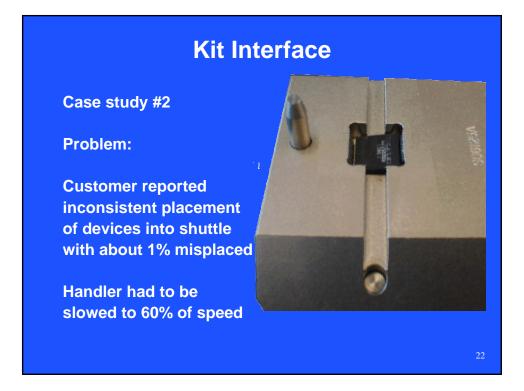
End Result: Yield returned to 88%-90%

Additional cost of test: \$13,725 (tester, technician time)



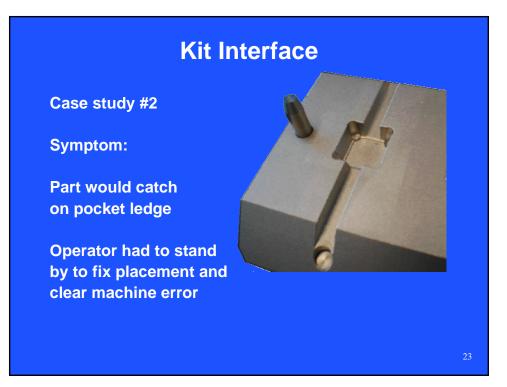
Exploring Handler, Socket & Device Interfacing

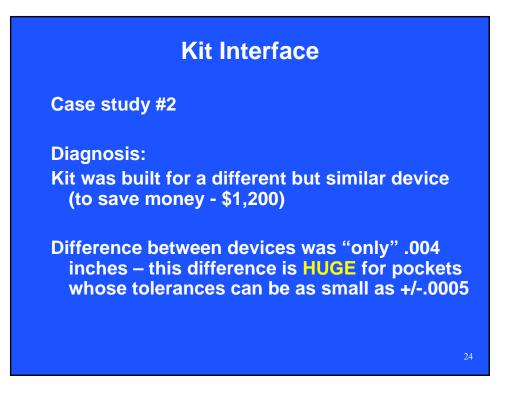






Exploring Handler, Socket & Device Interfacing

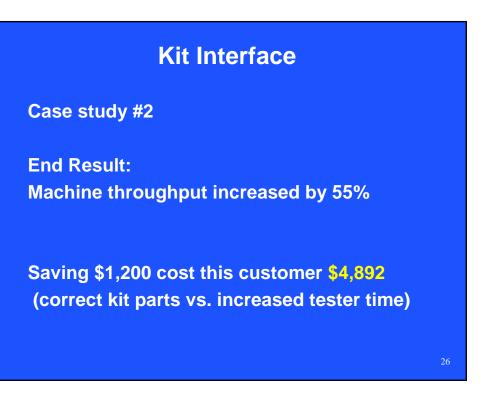






Exploring Handler, Socket & Device Interfacing

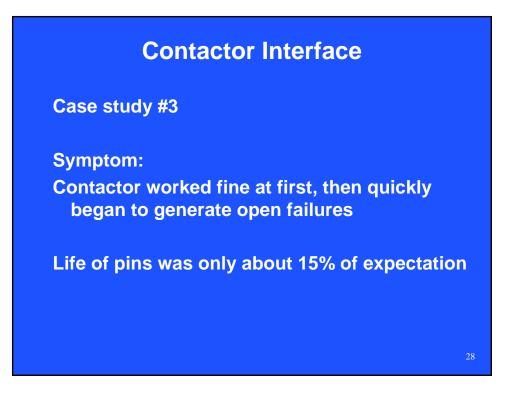
# <section-header><text><text><text><text><page-footer>





Exploring Handler, Socket & Device Interfacing

Contactor Interface
Case study #3
Problem: Customer reported premature "failure" of spring probe contactor
New socket "solved" problem
27





Exploring Handler, Socket & Device Interfacing

### **Contactor Interface**

Case study #3

**Diagnosis:** 

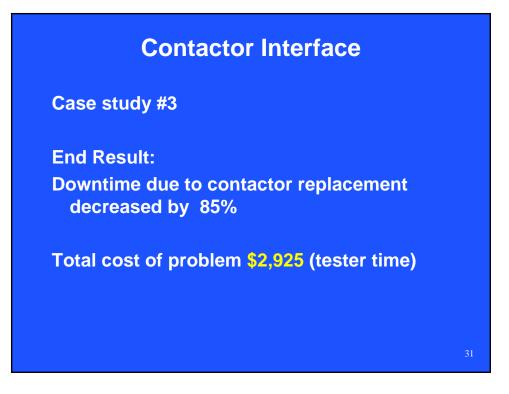
Hardstop / Workpress relationship was designed incorrectly

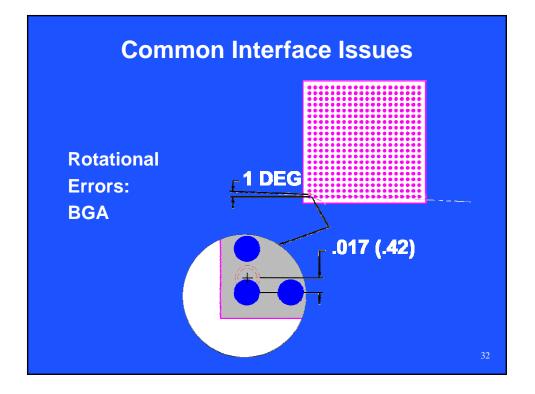
Device would make enough contact at first to work, then as springs lost some of their rate, balls would no longer make sufficient contact

# <section-header><text><text><text><text><text><text><text>



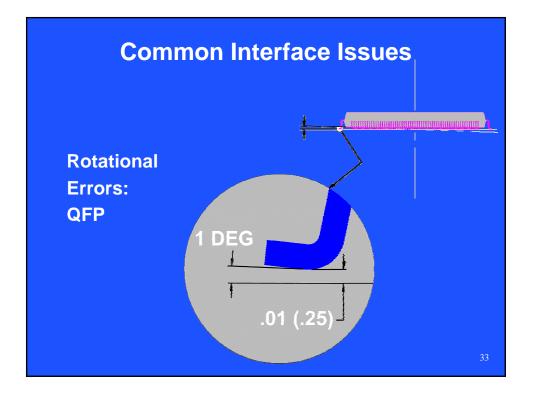
Exploring Handler, Socket & Device Interfacing

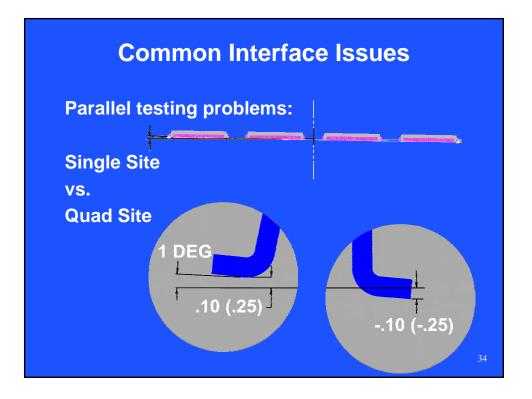






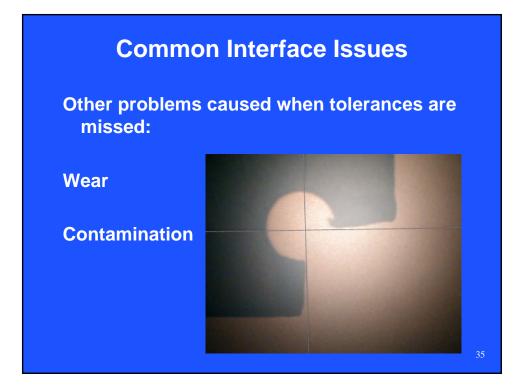
Exploring Handler, Socket & Device Interfacing

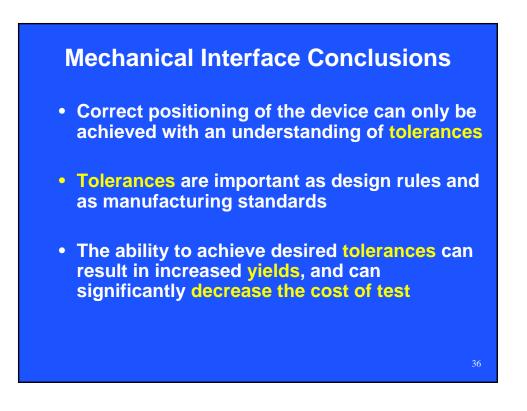






Exploring Handler, Socket & Device Interfacing







Exploring Handler, Socket & Device Interfacing





Exploring Handler, Socket & Device Interfacing

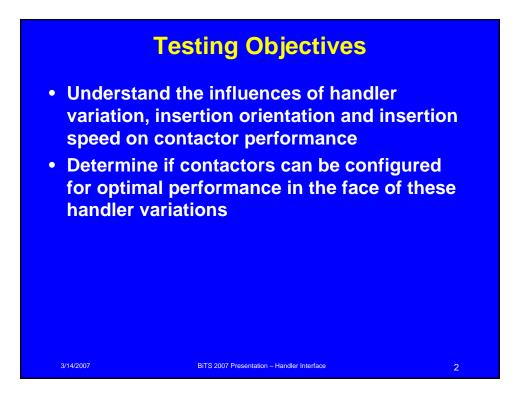
# Effects of Handler Insertion Variations on Contactor Performance for Pb – Free Devices

2007 Burn-in & Test Socket Workshop March 11 - 14, 2007



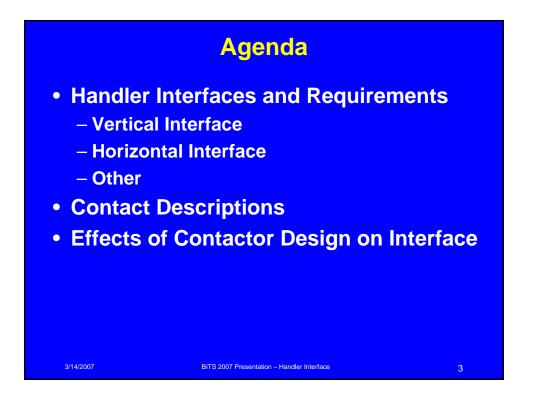
Jeff Sherry Johnstech International

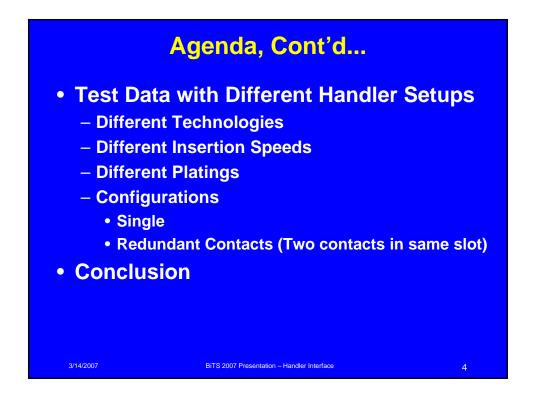
Johns<u>tech</u>°





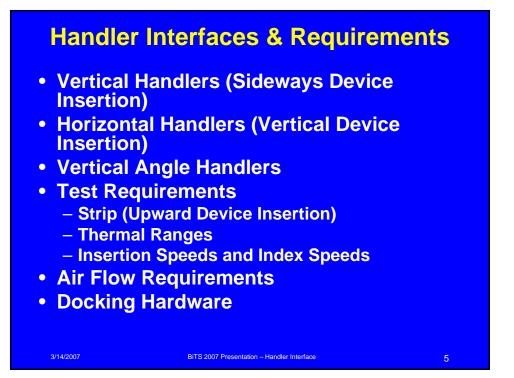
Exploring Handler, Socket & Device Interfacing

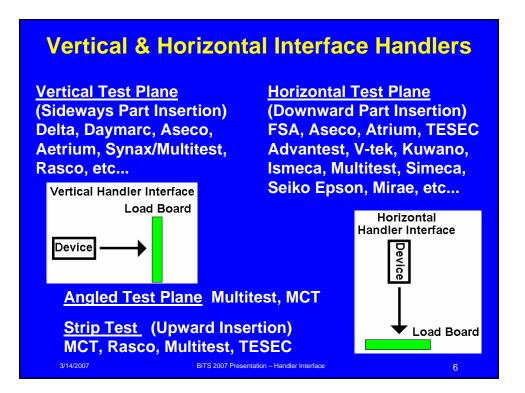






Exploring Handler, Socket & Device Interfacing

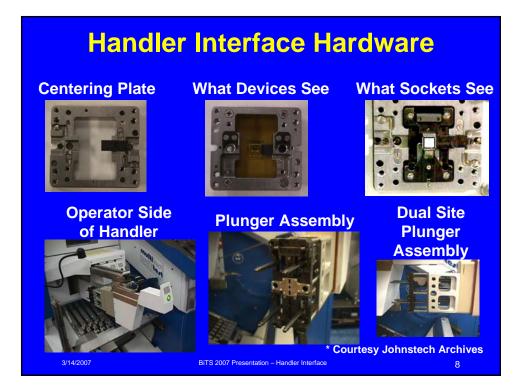






Exploring Handler, Socket & Device Interfacing







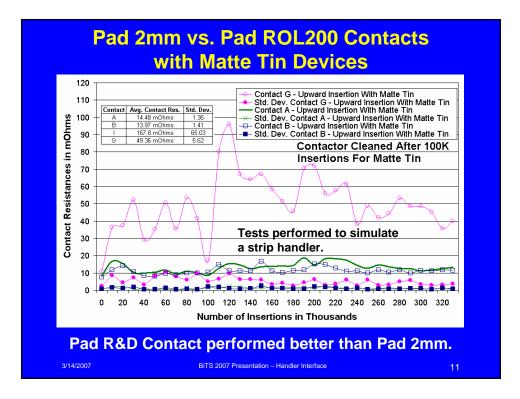
Exploring Handler, Socket & Device Interfacing

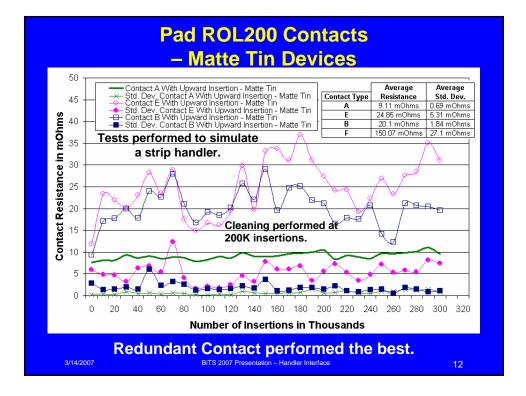
	Test Contact Des	criptions	
Contact	Description	Contact Material/Plating	Status
A	Redundant Contact — Pseudo Kelvin	Gold	R&D
В	Optimized Pad Contact	Gold	R&D
с	Pad ROL200 Fine Tip	Eco™-1	Released
D	Pad ROL200 Full Tip	Eco™-1	Released
E	Pad ROL200 Fine Tip	Gold	Released
F	Pad ROL200 Fine Tip	Gold / Rhodium*	R&D
G	Pad 2mm "S" Contact	Gold	Released
н	Leaded 2mm "S" Contact	Gold	Released
1	Pad 2mm "S" Contact	Gold / Rhodium*	R&D
	me Contact as the Gold-Plated dium Plating applied.	d Contact with	an extra
3/14/20	007 BiTS 2007 Presentation – Handler In	terface	9

	Test Matrix Design of Experiments Test Matrix								
	Design of Experiments Test Matrix								
Contact	Status	or Plating	Insertion Speeds	Elastomers	Device Platings	Device Insertion			
A	R&D	Gold	3.0 in/sec - 5.2 in/sec		Matte Tin	Downward			
В	R&D	Gold	8 in/sec - 11 in/sec	Low Force	NiPdAu	Sideways			
С	Released	Eco-1 <sup>™</sup>				Upward			
D	Released	Eco-1 <sup>™</sup>							
Е	Released	Gold							
F	R&D	Gold/Rhodium*							
G	Released	Gold							
Н	Released	Gold							
Ι	R&D	Gold/Rhodium*							
ntervals fo	r Matte Tin an	d at 300K for NiPd,	board, one insertion pe Au device testing. tra Rhodium plated app		ning was done at 1	00K or 200K			
- 6	68 Diffe	rent Com	ontact – Dev binations Te lared Johns	sted					
3/	14/2007		BiTS 2007 Presentation - Ha	ndler Interface		10			



Exploring Handler, Socket & Device Interfacing

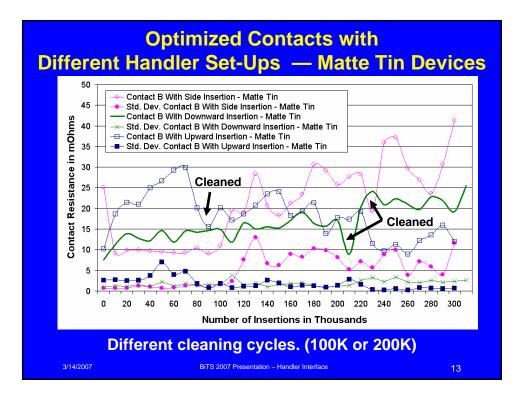


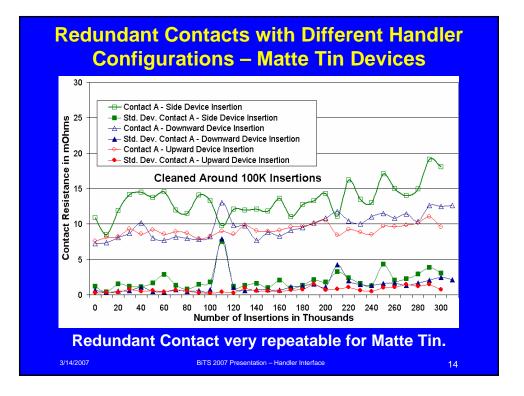






Exploring Handler, Socket & Device Interfacing







Exploring Handler, Socket & **Device Interfacing** 

### **Contact Summary for Handler Orientations** Matte Tin Devices

Handler Interface V	Handler Interface Vertical - Debris Collects on one side in Contactor - Sideways Device Insertion							
Contact Types	Contact Yield	Average Resistance	Std. Dev. Resistance	Yield < 20 mOhms				
В	99.04%	19.64 mOhms	13.00 mOhms	68.69%				
E	99.97%	21.32 mOhms	10.21 mOhms	68.97%				
A	99.90%	14.39 mOhms	4.39 mOhms	88.21%				
F	99.34%	128.83 mOhms	60.63 mOhms	0.81%				

Handler Interface H	Handler Interface Horizontal - Most Debris Collection in Contactor - Downward Device Insertion							
Contact Types	Contact Yield	Average Resistance	Std. Dev. Resistance	Yield < 20 mOhm				

Contact Types	Contact Yield	Average Resistance	Std. Dev. Resistance	Yield < 20 mOhms
В	100.00%	16.22 mOhms	4.45 mOhms	80.02%
E	100.00%	38.30 mOhms	23.51 mOhms	27.80%
A	99.99%	12.35 mOhms	4.78 mOhms	87.95%
F	100.00%	157.20 mOhms	68.20 mOhms	1.27%

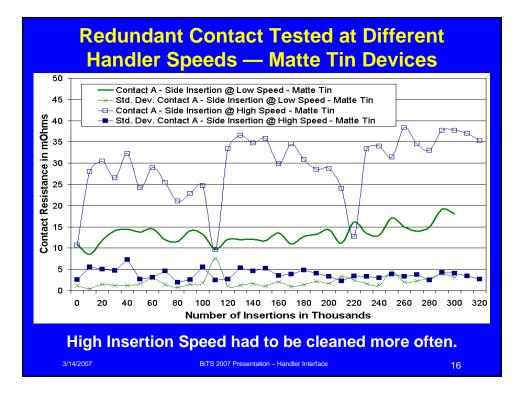
Handler Interface Horizontal - Debris Collects on Device - Upward Device Insertion

Contact Types	Contact Yield	Average Resistance	Std. Dev. Resistance	Yield < 20 mOhms
В	100.00%	19.65 mOhms	4.98 mOhms	53.41%
Ш	100.00%	24.20 mOhms	8.84 mOhms	44.11%
A	100.00%	11.009 mOhms	2.10 mOhms	99.14%
F	100.00%	160.88 mOhms	73.00 mOhms	0.56%

### **Redundant Contacts perform best.**

3/14/2007

BiTS 2007 Presentation – Handler Interface

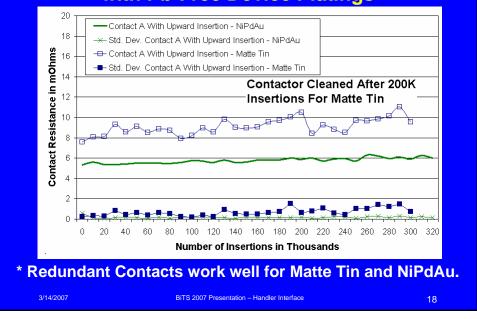




Exploring Handler, Socket & Device Interfacing

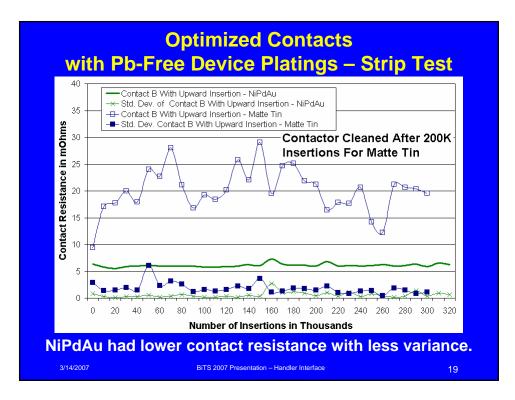
	Set-up			
		aning and Matte Tin D		
Contact Types	Contact Yield		Std. Dev. Resistance	
В	100.00%	12.93 mOhms	2.40 mOhms	99.28%
E	100.00%	21.26 mOhms	10.66 mOhms	60.47%
A	100.00%	8.65 mOhms	1.08 mOhms	99.97%
F Handler Interface Horizor	100.00%	112.84 mOhms	42.33 mOhms	3.44%
		er 100K and Matte Tin		
Contact Types	Contact Yield		Std. Dev. Resistance	
		16.22 mOhms	4.45 mOhms	80.02%
В	100.00%			
E	100.00%	38.30 mOhms	23.51 mOhms	27.80%
E A	100.00% 99.99%	38.30 mOhms 12.35 mOhms	23.51 mOhms 4.78 mOhms	27.80% 87.95%
E A F Handler Interface Horizor	100.00% 99.99% 100.00% ttal - Most Debris Col	38.30 mOhms 12.35 mOhms 157.20 mOhms Ilection in Contactor - I	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse	27.80% 87.95% 1.27% ertion
E A F Handler Interface Horizor	100.00% 99.99% 100.00% ttal - Most Debris Col	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse	27.80% 87.95% 1.27% ertion
E A F Handler Interface Horizor First 100K Insert	100.00% 99.99% 100.00% Mail - Most Debris Col	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas	27.80% 87.95% 1.27% ertion
E A F Handler Interface Horizor First 100K Insert Contact Types	100.00% 99.99% 100.00% ttal - Most Debris Col tions Without Cleanin Contact Yield	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic Average Resistance	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas Std. Dev. Resistance	27.80% 87.95% 1.27% ertion stomers Yield < 20 mOhm
E A F Handler Interface Horizor First 100K Insert Contact Types B	100.00% 99.99% 100.00% tal - Most Debris Col tions Without Cleanit Contact Yield 99.97%	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic Average Resistance 14.28 mOhms	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas Std. Dev. Resistance 18.94 mOhms	27.80% 87.95% 1.27% ertion tomers Yield < 20 mOhm 95.39%
E A F Handler Interface Horizor First 100K Insert Contact Types B E A F	100.00% 99.99% 100.00% tal - Most Debris Col ions Without Cleanit Contact Yield 99.97% 99.82% 100.00% 95.85%	38.30 mOhms 12.35 mOhms 157.20 mOhms Ilection in Contactor - I ng and Matte Tin Devid Average Resistance 14.28 mOhms 52.73 mOhms 16.65 mOhms 303.75 mOhms	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas Std. Dev. Resistance 18.94 mOhms 26.9 mOhms 6.73 mOhms 120.25 mOhms	27.80% 87.95% 1.27% ertion tomers Yield < 20 mOhm 95.39% 8.98%
E A F Handler Interface Horizor First 100K Insert Contact Types B E E A F P Handler Interface Horizor 300K Insertions W	100.00% 99.99% 100.00% ital - Most Debris Col ions Without Cleani Contact Yield 99.97% 99.82% 100.00% 95.85% ital - Debris Collects ithout Cleaning afte	38.30 mOhms 12.35 mOhms 157.20 mOhms Ilection in Contactor - I ng and Matte Tin Devic Average Resistance 14.28 mOhms 52.73 mOhms 303.75 mOhms 303.75 mOhms on Device - Upward Do r 100K and Matte Tin D	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inso ces - Lower Force Elas Std. Dev. Resistance 18.94 mOhms 26.9 mOhms 120.25 mOhms 120.25 mOhms evice Insertion	27.80% 87.95% 1.27% ention tomers Yield < 20 mOhm 95.39% 8.98% 86.40% 1.42% Elastomers
E A F Handler Interface Horizor First 100K Insert Contact Types B E A A F ' Handler Interface Horizor 300K Insertions W Contact Types	100.00% 99.99% 100.00% ttal - Most Debris Col ions Without Cleanin Contact Yield 99.97% 99.82% 100.00% 95.85% ttal - Debris Collects ithout Cleaning afte Contact Yield	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic Average Resistance 14.28 mOhms 52.73 mOhms 303.75 mOhms 303.75 mOhms on Device - Upward Do r 100K and Matte Tin D Average Resistance	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Insection Std. Dev. Resistance 18.94 mOhms 26.9 mOhms 120.25 mOhms 120.25 mOhms evice Insertion evices - Lower Force [Std. Dev. Resistance	27.80% 87.95% 1.27% ertion tomers Yield < 20 mOhm 95.39% 8.98% 86.40% 1.42% Elastomers Yield < 20 mOhm
E A F Handler Interface Horizor First 100K Insert Contact Types B E A F Handler Interface Horizor 300K Insertions W Contact Types B	100.00% 99.99% 100.00% ttal - Most Debris Col ions Without Cleanit Contact Yield 99.97% 99.82% 100.00% 95.85% ttal - Debris Collects ithout Cleaning afte Contact Yield 99.38%	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic Average Resistance 14.28 mOhms 52.73 mOhms 303.75 mOhms on Device - Upward Do r 100K and Matte Tin D Average Resistance 71.73 mOhms	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas Std. Dev. Resistance 18.94 mOhms 2.89 mOhms 6.73 mOhms 120.25 mOhms evice Insertion evices - Lower Force Std. Dev. Resistance 73.02 mOhms	27.80% 87.95% 1.27% Prtion tomers 95.39% 8.99% 86.40% 1.42% Elastomers Yield < 20 mOhm 40.19%
E A F Handler Interface Horizor First 100K Insert Contact Types B E A A F P Handler Interface Horizor 300K Insertions W Contact Types B E	100.00% 99.99% 100.00% ttal - Most Debris Col ions Without Cleanin 99.97% 99.82% 100.00% 95.85% ttal - Debris Collects ithout Cleaning afte Contact Yield 99.98% 99.98%	38.30 mOhms 12.35 mOhms 157.20 mOhms Istration in Contactor - I and Matte Tin Devic Average Resistance 14.28 mOhms 52.73 mOhms 303.75 mOhms on Device - Upward Do r 100K and Matte Tin D Average Resistance 71.73 mOhms 92.78 mOhms	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas Std. Dev. Resistance 18.94 mOhms 6.73 mOhms 120.25 mOhms evice Insertion evices - Lower Force Std. Dev. Resistance 73.02 mOhms 58.75 mOhms	27.80% 87.95% 1.27% ention tomers Yield < 20 mOhm 95.33% 8.98% 86.40% 1.42% Elastomers Yield < 20 mOhm 40.19% 7.64%
E A F Handler Interface Horizor First 100K Insert Contact Types B E A F Handler Interface Horizor 300K Insertions W Contact Types B	100.00% 99.99% 100.00% ttal - Most Debris Col ions Without Cleanit Contact Yield 99.97% 99.82% 100.00% 95.85% ttal - Debris Collects ithout Cleaning afte Contact Yield 99.38%	38.30 mOhms 12.35 mOhms 157.20 mOhms lection in Contactor - I ng and Matte Tin Devic Average Resistance 14.28 mOhms 52.73 mOhms 303.75 mOhms on Device - Upward Do r 100K and Matte Tin D Average Resistance 71.73 mOhms	23.51 mOhms 4.78 mOhms 68.20 mOhms Downward Device Inse ces - Lower Force Elas Std. Dev. Resistance 18.94 mOhms 2.89 mOhms 6.73 mOhms 120.25 mOhms evice Insertion evices - Lower Force Std. Dev. Resistance 73.02 mOhms	27.80% 87.95% 1.27% Prtion tomers 95.39% 8.99% 86.40% 1.42% Elastomers Yield < 20 mOhm 40.19%

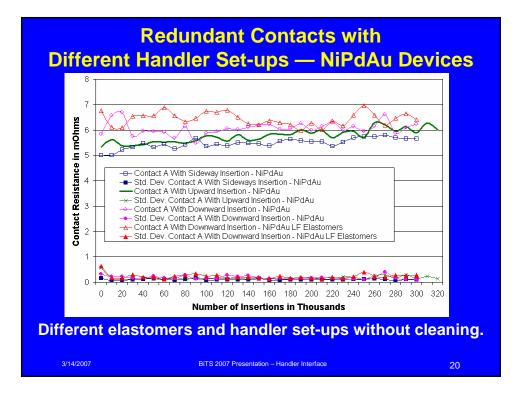
### Redundant Contacting (Pseudo Kelvin) with Pb-Free Device Platings





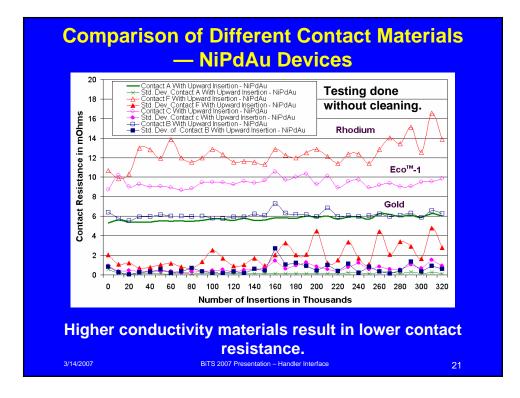
Exploring Handler, Socket & Device Interfacing







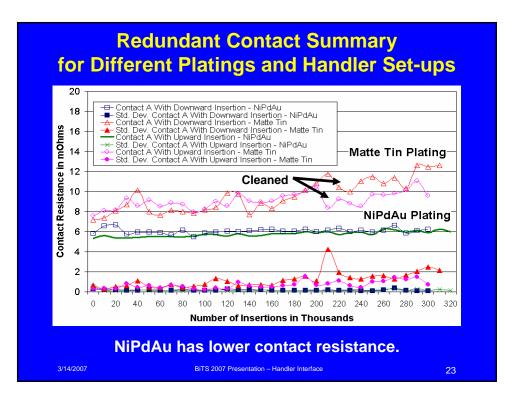
Exploring Handler, Socket & Device Interfacing

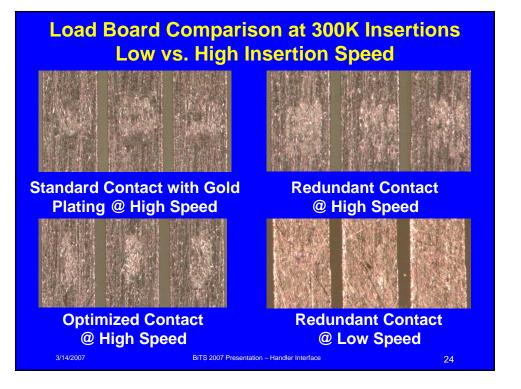


Contact Type A F C D	Contact Yield 100.00% 99.98% 98.92%	Average Resistance 5.5 mOhms	Std. Dev. Resistance	Yield < 20 mOhms
F C D	99.98%	5.5 mOhms		
C D			0.28 mOhms	100.00%
D		12.67 mOhms	11.63 mOhms	92.37%
		31.25 mOhms	53.81 mOhms	68.13%
	99.99%	6.82 mOhms one side in Contactor	0.51 mOhms	99.99%
		thout Cleaning and Nil		
Contact Type	Contact Yield		Std. Dev. Resistance	
F	99.97%	5.89 mOhms	0.52 mOhms	99.97%
	99.84%	13.4 mOhms	4.46 mOhms	94.30%
<u>с</u>	99.95% 99.84%	10.15 mOhms 10.91 mOhms	3.18 mOhms 10.62 mOhms	98.97% 94.51%
Handler Interface Horizo				-d Electronica
Contact Type	300K Insertions Wi	thout Cleaning and Nil Average Resistance	PdAu Devices - Standa Std. Dev. Resistance	Yield < 20 mOhms
Contact Type A	300K Insertions Wi Contact Yield 99.97%	thout Cleaning and Nil Average Resistance 6.26 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms	Yield < 20 mOhms 99.95%
Contact Type A F	300K Insertions Wi Contact Yield 99.97% 99.96%	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.32 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 7.99 mOhms	Yield < 20 mOhms 99.95% 99.20%
Contact Type A F C	300K Insertions Wi Contact Yield 99.96% 99.96% 99.04%	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.32 mOhms 10.93 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 7.99 mOhms 13.21 mOhms	Yield < 20 mOhms 99.95% 99.20% 98.25%
Contact Type A F C D	300K Insertions Wi Contact Yield 99.97% 99.96% 99.04% 99.05%	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.32 mOhms 10.93 mOhms 12.51 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 7.99 mOhms 13.21 mOhms 8.44 mOhms	Yield < 20 mOhms 99.95% 99.20% 98.25% 97.90%
Contact Type A F C	300K Insertions Wi Contact Yield 99.97% 99.96% 99.04% 99.05% Intal - Most Debris Col	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.32 mOhms 10.93 mOhms 12.51 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 7.99 mOhms 13.21 mOhms 8.44 mOhms Downward Device Inst	Yield < 20 mOhms           99.95%           99.20%           98.25%           97.90%           ertion
Contact Type A F C D Handler Interface Horizo Contact Type	300K Insertions Wi Contact Yield 99.97% 99.04% 99.04% 99.05% Intal - Most Debris Col 300K Insertions Wi Contact Yield	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.32 mOhms 12.51 mOhms Ilection in Contactor - thout Cleaning and Nil Average Resistance	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 7.99 mOhms 13.21 mOhms 8.44 mOhms Downward Device Inser PdAu Devices - Low Fr Std. Dev. Resistance	Yield < 20 mOhms           99.95%           99.20%           98.25%           97.90%           ertion
Contact Type A F C D Handler Interface Horizo Contact Type A	300K Insertions Wi Contact Yield 99.97% 99.04% 99.04% 99.05% ontal - Most Debris Col 300K Insertions Wi Contact Yield 99.99%	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.93 mOhms 12.51 mOhms Ilection in Contactor - thout Cleaning and Nil Average Resistance 6.4 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 13.21 mOhms 8.44 mOhms Downward Device Inse PdAu Devices - Low Fo Std. Dev. Resistance 0.42 mOhms	Yield < 20 mOhms           99.95%           99.20%           98.25%           97.90%           ertion           orce Elastomer           Yield < 20 mOhms
Contact Type A F C D Handler Interface Horizo Contact Type A F	300K Insertions Wi Contact Yield 99.97% 99.04% 99.04% 99.05% Intal - Most Debris Col 300K Insertions Wi Contact Yield 93.99% 93.92%	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.93 mOhms 12.51 mOhms Ilection in Contactor -1 thout Cleaning and Nil Average Resistance 6.4 mOhms 12.22 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 13.21 mOhms 8.44 mOhms Downward Device Inse PdAu Devices - Low Fr Std. Dev. Resistance 0.42 mOhms 5.34 mOhms	Yield < 20 mOhms
Contact Type A F C D Handler Interface Horizo Contact Type A	300K Insertions Wi Contact Yield 99.97% 99.04% 99.04% 99.05% ontal - Most Debris Col 300K Insertions Wi Contact Yield 99.99%	thout Cleaning and Nil Average Resistance 6.26 mOhms 10.93 mOhms 12.51 mOhms Ilection in Contactor - thout Cleaning and Nil Average Resistance 6.4 mOhms	PdAu Devices - Standa Std. Dev. Resistance 0.38 mOhms 13.21 mOhms 8.44 mOhms Downward Device Inse PdAu Devices - Low Fo Std. Dev. Resistance 0.42 mOhms	Yield < 20 mOhms           99.95%           99.20%           98.25%           97.90%           ertion           orce Elastomer           Yield < 20 mOhms



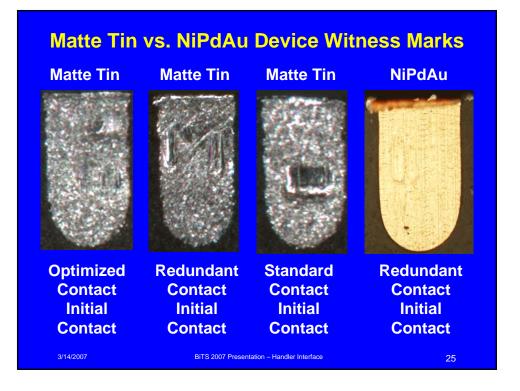
Exploring Handler, Socket & Device Interfacing







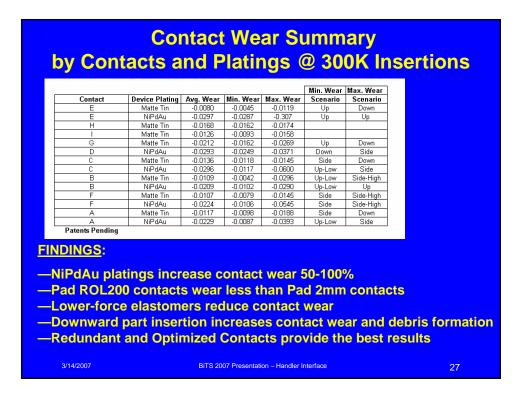
Exploring Handler, Socket & Device Interfacing

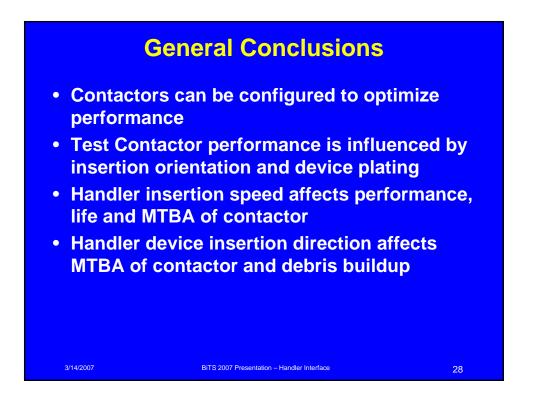


Redun	dant vs. O	ptir	nized	Conta	acts	
Contact A — F	Redundant Co	onta	ct - NiP	dAu		
	Pseudo Kelvin (Redundant Co Average Contact Resistance	ontact)	Performance o Sideways 5.5 mOhms	of Insertion Type Downward 6.26 mOhms		
17	Std. Dev. Contact Yield Yield < 20 mOhms		0.28 mOhms 100% 100%	0.38 mOhms 99.97% 99.95%	Minimal wear after	
	Summary After 300K Insertions With NO Cleaning With NPdAu Plated Devices					
9	Max Positive				Insertions!!	
	Max Negative				Data summar	у
Contact B — C	optimized Co				is for 300K	
	Optimized Contact Average Contact Resistance	Perfo	rmance	Force Elastomers Performance 14.28 mOhms	insertions w/o	þ
87	Std. Dev. Contact Yield Yield < 20 mOhms	10	nOhms 10% 28%	7.118 mOhms 99.97% 95.39%	cleaning.	
	Electrical Performance		mance @ 20 GHz	Performance		
5	Return Loss Crosstalk	-1 dB @	31.6 GHz 16.8 GHz 2 22 GHz			
	Max Positive			0.0182		
	Max Negative			-0.0084		
*Results measured 3/14/2007	by GateWave No BiTS 2007 Present				26	



Exploring Handler, Socket & Device Interfacing









Exploring Handler, Socket & Device Interfacing

### **Conclusions After 20M Insertions**

- Rhodium-Plated contacts are ineffective and perform poorly for Matte Tin plated devices
- Rhodium plating (1,000X harder than Gold) does not work on contacts with sharp edges but could be used as selective board plating or on contacts interfacing to NiPdAu device pads, for longer life
- Optimized contacts and Redundant (Pseudo Kelvin) contacts work well and need less maintenance on Matte Tin applications
- Redundant contact results and performance are very repeatable and may be good enough for many applications requiring low and stable contact resistance over large cycle counts

 For more information contact www.johnstech.com

 3/14/2007
 BITS 2007 Presentation - Handler Interface
 29



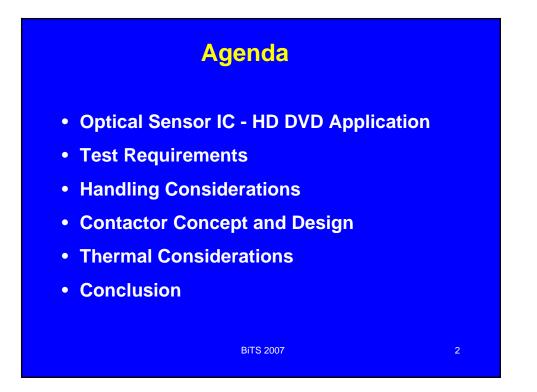
Exploring Handler, Socket & Device Interfacing

# Contacting Solution for Optical Sensor IC -HD DVD Application

2007 Burn-in and Test Socket Workshop March 11 - 14, 2007

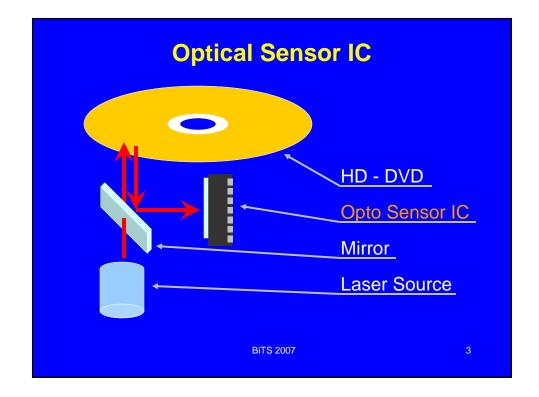


Gerhard Gschwendtberger Multitest elektronische Systeme GmbH





Exploring Handler, Socket & Device Interfacing



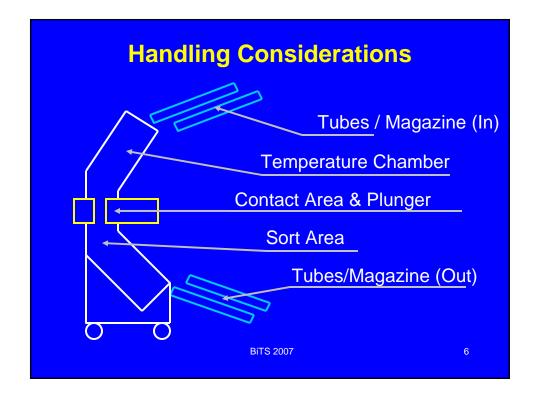
# <section-header><section-header><section-header><section-header><section-header><section-header><list-item><list-item><list-item><section-header><section-header><section-header>



Exploring Handler, Socket & Device Interfacing

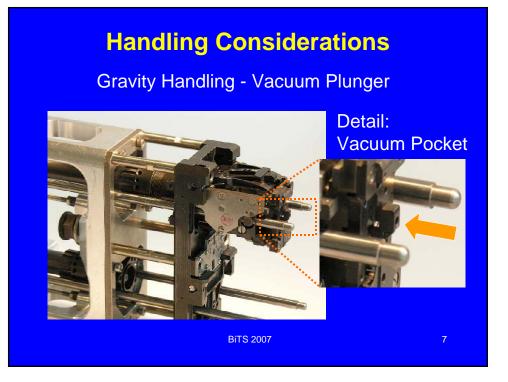
### **Handling Considerations**

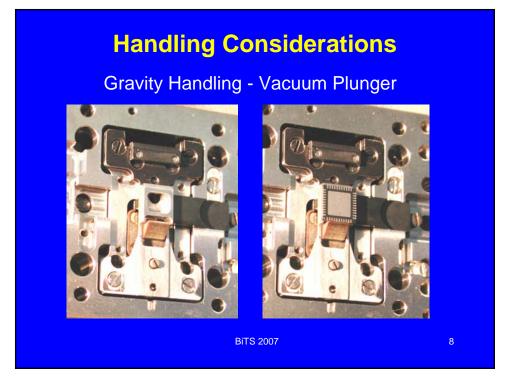






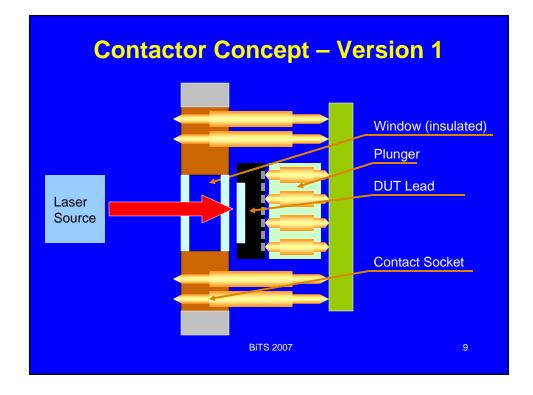
Exploring Handler, Socket & Device Interfacing

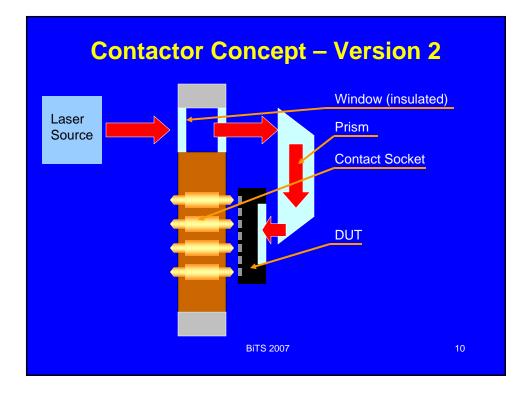






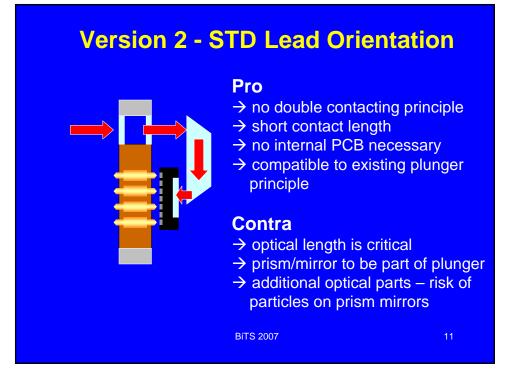
Exploring Handler, Socket & Device Interfacing

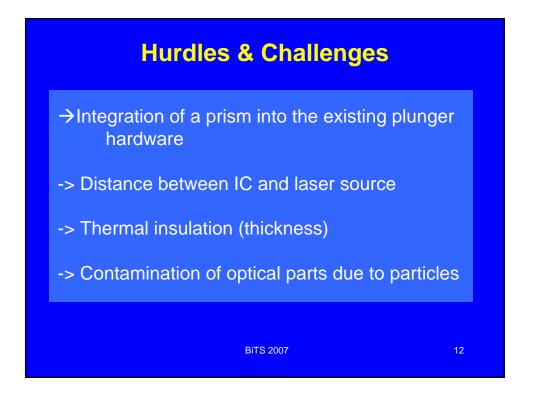






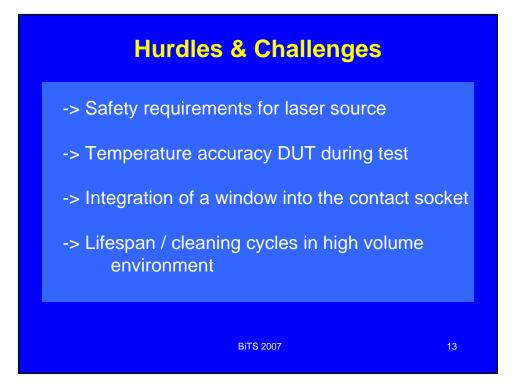
Exploring Handler, Socket & Device Interfacing

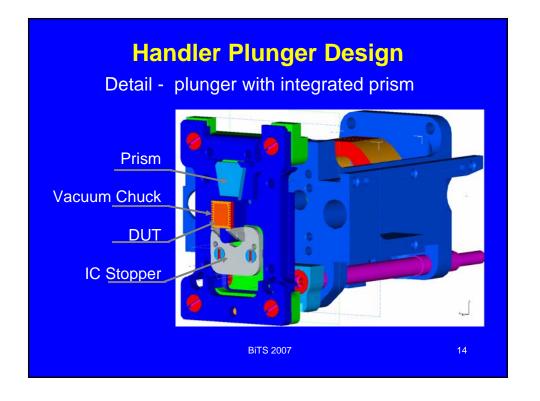






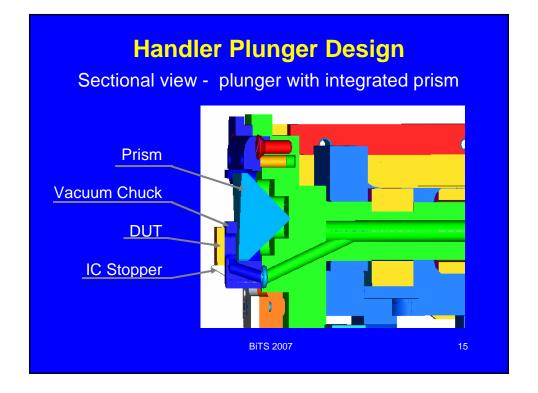
Exploring Handler, Socket & Device Interfacing

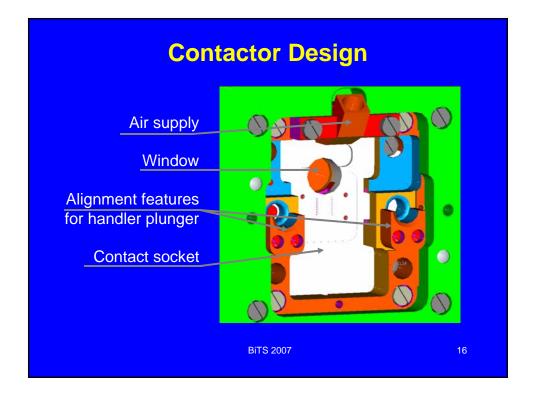






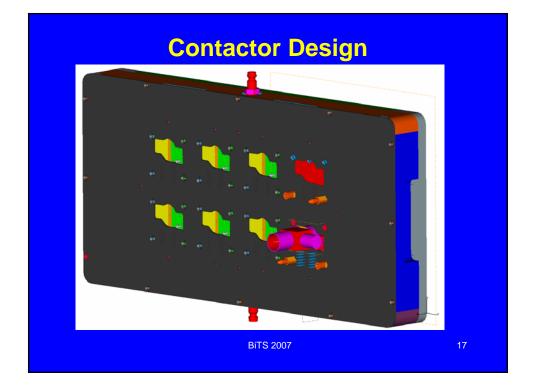
Exploring Handler, Socket & Device Interfacing

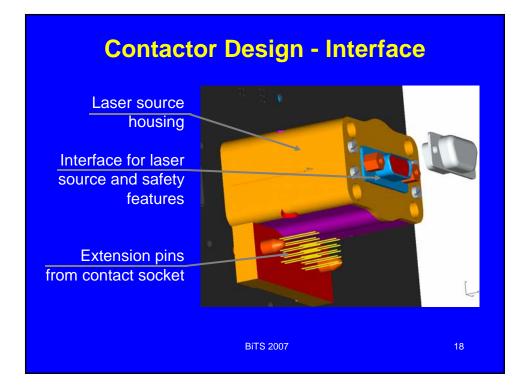






Exploring Handler, Socket & Device Interfacing

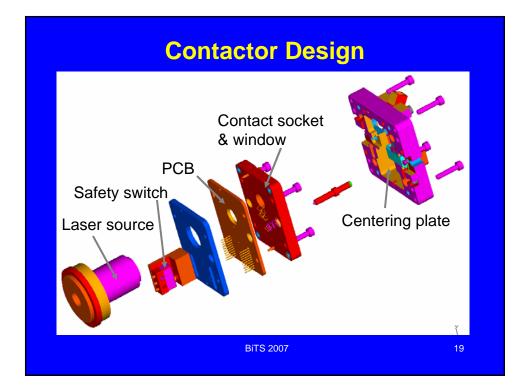


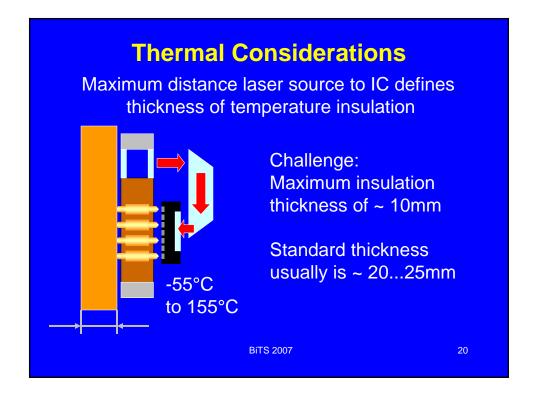






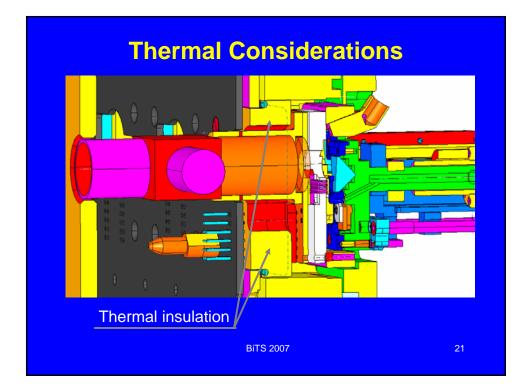
Exploring Handler, Socket & Device Interfacing

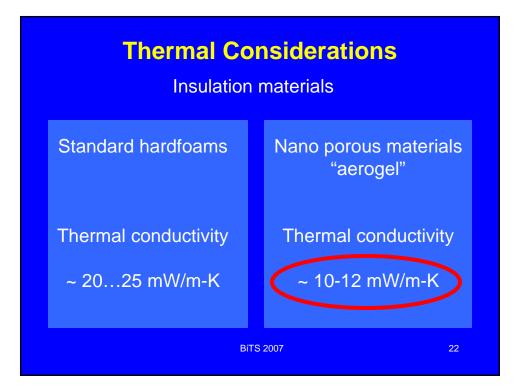






Exploring Handler, Socket & Device Interfacing







Exploring Handler, Socket & Device Interfacing

